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Attorney's Docket No.: 10559-882001/P17484  
Intel Corporation

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Yan Borodovsky                          Art Unit: 1756  
Serial No.: 10/693,373                              Examiner:  
Filed        : October 24, 2003  
Assignee     : Intel Corporation  
Title        : COMPOSITE OPTICAL LITHOGRAPHY METHOD FOR PATTERNING  
                  LINES OF UNEQUAL WIDTH

**Mail Stop Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information Disclosure Statement and documents listed on form PTO-1449.

This filing is being made before the receipt of a first Office action on the merits. No fee is required.

The documents are in the English language; hence no concise explanation is necessary per Rule 98(a)(3).

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the

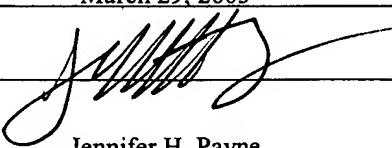
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Applicant : Yan Borodovsky  
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Examiner's initials in the left column per MPEP 609 are  
earnestly solicited along with an early action on the merits.

Please apply any additional charges or credits to Deposit  
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Respectfully submitted,

  
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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-882001	Application No. 10/693,373
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))		Applicant Yan Borodovsky	P A T E N T & T R A D E M A R K O F F I C E M A R 3 1 2 0 0 5 J. Casper
		Filing Date October 24, 2003	

<b>U.S. Patent Documents</b>							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						

<b>Foreign Patent Documents or Published Foreign Patent Applications</b>							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation Yes      No
	AE						
	AF						
	AG						

<b>Other Documents (include Author, Title, Date, and Place of Publication)</b>		
Examiner Initial	Desig. ID	Document
	AH	M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.
	AI	J.A. Hoffnagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.
	AJ	Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.
	AK	Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.
	AL	Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.
	AM	Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1=0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.
	AN	M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.
	AO	Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.
	AP	Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.
	AQ	M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging," Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005.

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	